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ACTION

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(54) Title: POST CHEMICAL-MECHANICAL PLANARIZATION (CMP) CLEANING COMPOSITION

(57) Abstract: A cleaning solution for cleaning microelectronic substrates, particularly for post-CMP or via formation cleaning. The cleaning solution comprises a quaternary ammonium hydroxide, an organic amine, a corrosion inhibitor, optionally an organic acid, and water. A preferred cleaning solution comprises tetramethylammonium hydroxide, monoethylanolamine, gallic acid ascorbic acid, and water with the alkalinity of the cleaning solution greater then 0.073 milliequivalents base per gram of solution.